

## AMENDMENTS TO THE CLAIMS

**Claim 1 (Original)** A substrate processing system comprising:

a gas supply source for supplying a process gas containing a reactive substance;

a reservoir tank connected to said gas supply source for reserving said process gas;

a reactor for exposing a substrate placed therein to said process gas;

a first circulation pipe for introducing the process gas inside said reactor into said reservoir tank;

a second circulation pipe for introducing at least part of the process gas in said reservoir tank into said reactor; and

a flow regulating valve disposed in said second circulation pipe for regulating the amount of process gas to be introduced into said reactor.

**Claim 2 (Original)** The substrate processing system of Claim 1, further comprising a pump for drawing said process gas from said reactor and introducing it into said reservoir tank through said first circulation pipe.

**Claim 3 (Currently Amended)** The substrate processing system of Claim 1 or 2, further comprising a second gas supply source for supplying a second process gas to said reactor such that the second process gas bypasses said reservoir tank, said second process gas containing a reactive substance different from that contained in said first process gas.

**Claim 4 (New)** The substrate processing system of Claim 2, further comprising a second gas supply source for supplying a second process gas to said reactor such that the second process gas bypasses said reservoir tank, said second process gas containing a reactive substance different from that contained in said first process gas.